

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Jiutao Li et al.

Group Art Unit: 1795

Application No.: 10/712,106

Examiner: Rodney Glenn McDonald

Filed: November 14, 2003

Confirmation No.: 8216

For: SILVER SELENIDE SPUTTERED FILMS AND
METHOD AND APPARATUS FOR
CONTROLLING DEFECT FORMATION IN
SILVER SELENIDE SPUTTERED FILMS

Allowed: April 22, 2010

**COMMENTS ON EXAMINER'S
STATEMENT OF REASONS FOR ALLOWANCE**

MS Issue Fee
Commissioner of Patents
P.O. Box 1450
Alexandria, VA 22313-1450


Dear Sir:

Applicants agree in part with the Examiner's statement of reasons for allowance in that the prior art of record fails to anticipate or render obvious the claimed invention. However, Applicants note that the Examiner's statement fails to address all limitations of all of the allowed claims. For example, certain claim limitations were not discussed in the Examiner's reasons for allowance, including those in the dependent claims, each of which defines a unique combination of features not shown or suggested by the prior art, providing additional reasons for allowance of each claim.

Applicants submit that the scope of the claims should be interpreted based on the actual language of the allowed claims, and no further limitation of the claims should be inferred from the Examiner's Statement of Reasons For Allowance.

Dated: July 21, 2010

Respectfully submitted,

By 
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